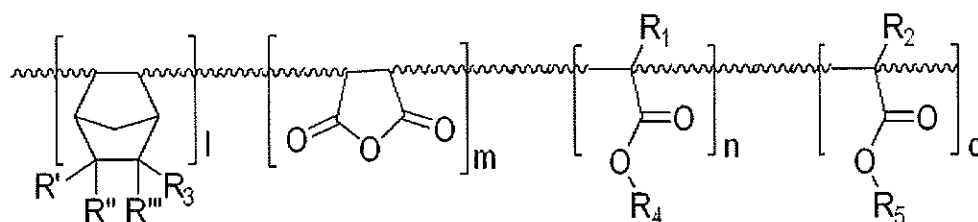


ABSTRACT

ADDITIVE FOR RESIST AND RESIST COMPOSITION COMPRISING SAME

A resist additive represented by Formula 1 below and a resist composition including the additive are disclosed. The resist additive improves hydrophobicity of the surface of the resist film to prevent materials from being leached in water during exposure of immersion lithography and is converted to have hydrophilicity by deprotection reaction during development. As a result, a micropattern of a resist film with excellent sensitivity and high resolution is formed.

Formula 1



In Formula 1, the substituents are defined as described in the specification.